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Simulation and development of a coded source neutron imaging system

Introduction Coded Source Imaging

Coded aperture imaging (CAI) is a well researched method for imaging sources and has been applied in areas from astronomy to homeland security. CAI uses a coded aperture (CA) with many pinholes in a well defined pattern to image the source onto a detector. Multiple pinholes allow improved signal on the detector from the source, but results in a coded image. CAs such as uniformly redundant arrays have been designed that have a defined decode kernel to reconstruct the source and have an open aperture of 50%. Coded source imaging (CSI) places a CA between an illumination source and an object to be imaged. This allows the object to be imaged with many high resolution pinholes for magnified imaging without the loss in flux associated with a single pinhole. The resulting coded radiograph follows the same math as CAI allowing use of the CAs and decode kernels already developed for CAI.



Simulation

A series of simulations have been performed to understand performance of CSI for neutron imaging. Simulations are being performed with First simulations were performed McStas. imaging a single pinhole object. Imaging pinhole results in an image of the aperture which allowed debugging and pattern verification of the model with theoretical calculations.



CAI provide perfect reconstruction for single point sources, so a set of simulations was performed with arrays of pinholes to evaluate performance as an object becomes more extended. In these simulations, the source is uniform and the detector resolution high enough to ignore such that performance depends on the object and reconstruction. The coded aperture is a 47x47 MURA pattern with 100µm pitch. Objects are pinhole arrays with $50\mu m$ diameter holes. Four simulations were performed with different pinhole spacing.



Simulation of pinhole arrays (top row) CA images of 4x4 array and 21x21 array (bottom row) reconstructed images for arrays with hole spacing of 950µm, 475µm, 237.5µm, and 142.5µm

quantitative measurement of resolution resulting from the CAI system, simulations of a tilted edge were performed. After reconstructing the image, a line edge function was extracted from the image and processed to provide the modulation transfer function (MTF). Simulations were performed with a $10\mu m$ and a 100µm CA mask. Using a 10% contrast level cutoff, resolution for the 10µm mask is at 50 line pairs/mm ($10\mu m$).





(Top left) Simulated CA image of tilted edge object, (Bottom left) image from reconstruction, and (Left) MTF calculation for 10µm and 100µm CA simulations

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Development of a two stage system to facilitate movement of the aperture pair and the object has been completed and tested during experiments. Designs for coded apertures to be used at HFIR have been selected based on beam parameters measured in earlier tests.

A major development challenge for development is the manufacture of CA patterns with resolutions in the 1-10µm range. Investigation of manufacture methods has lead to semiconductor manufacturing capabilities. Working with CNMS at ORNL, first tests at sputtering Gd on a Si wafer were very successful at 1μ m thickness.



Si wafer with Gd masking material and Ti to prevent oxidization of Gd

Left) comparison

1mm pinhole

inhole without

both of these stations.

CG1A was set up with a magnification of 6.48. With this setup, resolution is to be 322µm. expected Images are shown simulation results for comparison. The aperture pattern is noticeably dim on the top left and bottom right corners of the images. An image taken without coded apertures shows the non-uniformity of the beam.

Initial experiments imaging a 1mm diameter pinhole object have been performed at both stations. Non-uniformity of illumination is a concern for





Reconstruction of the pinhole is relatively unaffected by the non-uniformity as the central portion of this image is all that is required for reconstruction. The 1mm pinhole reconstruction is shown below with a line extracted across the pinhole. Based on pixel size of the detector and magnification of the system, the reconstructed hole size is 0.929mm which is well within the expected resolution.

Images were also taken of a line Reconstructions of object. extended objects are degraded significantly by the illumination uniformity and algorithm work is underway to develop methods for normalization.



(Left) 1mm pinhole reconstruction (Right) line through center of reconstructed pinhole

High resolution aperture development

Success of sputtering 1µm of Gd on Si wafer indicates thicknesses of 10µm or more are achievable. Testing of methods for etching materials are schedule to begin this month to determine resolution and thickness limitations.

High energy gammas result from neutron interactions with Gd, so shielding needs to be developed for the high resolution mask. Selection and inclusion of a perpendicular x-ray radiography system.



Initial plan for coded aperture wafer to include multiple aperture designs and testing features